



UNIUNEA EUROPEANĂ



GUVERNUL ROMÂNIEI



INSTRUMENTE STRUCTURALE
2007-2013

Programul Operațional Sectorial
"Creșterea Competitivității Economice"
"Investiții pentru viitorul dumneavoastră"

POS CCE: 665/12609/209/20.07.2010

Refractometer for layer thickness measurements

NanoCalc-XR

MICRONANOFAB

GENERAL CHARACTERISTICS:

- ✓ Transmission and reflection measurements of anti-reflective & hardness coatings
- ✓ Wide wavelength measurements (250nm to 1050 nm)
- ✓ Can measure up to 10 layer stacks
- ✓ Angle of incidence: 90°

APPLICATIONS

- ✓ Thickness measurements:
 - Silicon oxide
 - Silicon nitride
 - photoresist masks
 - metal films
- ✓ Single wafer measurements.
- ✓ Can measure thin films on non-planar surfaces



PERFORMANCE:

- ✓ Resolution: 0.1 nm
- ✓ Thickness range: 10nm to 100μm
- ✓ Defect and roughness tolerant measurements
- ✓ Database for a broad range of materials
- ✓ Fast measurement process: 100ms to 1s

ADVANTAGES:

- ✓ Easy to use
- ✓ Wide measurements range
- ✓ Can measure thicknesses for a wide range of materials
- ✓ Small footprint: light and portable
- ✓ Assisted by powerful computational software

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www.imt.ro/MICRONANOFAB

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